

Fixing Double Patterning Violations With Look-Ahead

Sambuddha Bhattacharya Subramanian Rajagopalan Shabbir Batterywala

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Introduction

Double Patterning Technology (DPT) must at 20nm and below

- Shapes assigned to two masks
- Shapes on same mask must have large separation

Mask assignment can have conflicts (DPT conflicts)

- Conflicts expressed as odd cycles
- Need to resolve conflicts for manufacturing
- Resolve by decomposition or legalization







Fixing DPT Conflicts: Approaches

- Layout Decomposition
 - optimal stitch insertion *
 - Overlap problem
- Layout Legalization
 - Increased spacing
 - Apt during early layout creation
- Combined Decomposition and Legalization
 - Simultaneous stitching and spacing #
 - Stitching followed by legalization [@]
- This work address some issues in legalization method
 - Prevents new DRC creation
 - Avoids new DPT conflict creation
- * Tang et al, "Optimal layout decomposition for double patterning technology," ICCAD 2011
- # Yuan et al, "Wisdom: Wire-spreading enhanced decomposition of masks in double patterning lithography," ICCAD 2010.
- @ Ghaida et al, "Layout decomposition and legalization for double-patterning technology," TCAD Feb 2013.





Challenges in Legalization Methods



Contracting



Need to carefully select location for increasing spacing

Layout Legalization: Flow and Model



Framework to modify layouts in a design-rule aware way

Layout Legalization in Presence of DPT





Possible Iterative Approach



Need a way to up-front know 'good' and 'bad' modifications

Look-Ahead Approach



Replaced external iterations. Predict spacing shrinkage

Graph Interactions



Feedback scheme to tighten constraints to meet DPT requirements

Predicting Spacing Shrinkage

- Run modified Bellman-Ford algorithm *
 - Initialize constraint graph nodes with input layout locations
 - In Forward run, update if 'relaxed' to value above input layout position
 - Forward run produces upper bound
 - In reverse run, update if 'relaxed' to a value below input layout position
 - Reverse run produces lower bound



• Potential DPT if : $\Delta UB \leq DPT \quad \forall \quad \Delta LB \leq DPT \quad and \quad \Delta LYT \geq DPT$

* Salodkar et al, "Automatic Design Rule Correction in Presence of Multiple Grids and Track Patterns", DAC 2013

Results

Expt.	#Lyt obj	#Nodes	#Edges	Input DPT	Input DRC	Output DPT	Output DRC	Runtime
1	634	2513	14840	150	182	0	0	0.45 s
2	1354	5393	32257	330	370	0	0	1.49 s
3	1854	7173	41206	459	529	1	4	4.86 s
4	2654	9953	59594	635	750	40	100	5.87 s
5	3946	13749	80391	854	1066	40	19	12.83 s

Expt.	Simple Le	galization	Look-ahead Legalization		
	Output DPT	Output DRC	Output DPT	Output DRC	
1	30	0	0	0	
2	70	0	0	0	
3	115	4	1	4	
4	170	100	40	100	
5	234	19	40	19	

Look-ahead helps fix many more DPT conflicts

Conclusions

- Proposed a method to fix DPT conflicts
 Based on legalization
- Looks ahead to
 - Avoid creating new DPT conflicts
 - Avoid creating DRC violations

Thank You